IN THE SPECIFICATION:

On page 1, please amend the first paragraph as follows:

"This application is a continuation of U.S. Serial No. 09/837,035 filed April 18, 2001 and is a continuation-in-part of Serial No. 09/748,316, filed December 22, 2000, now U.S. Patent No. 6,477,193, Serial No. 684,629 filed October 6, 2000, now U.S. Patent No. 6,442,181 and Serial No. 09/370,739, filed August 9, 1999, now U.S. Patent No. 6,151,346 which was a continuation-in-part of Serial No. 09/118,773, filed July 18, 1998 now U.S. Patent No. 5,936,988 and Serial No. 09/608,543, filed June 30, 2000, all of which are incorporated by reference herein. This invention relates to gas discharge lasers and in particular to high repetition rate gas discharge lasers.

Page 4 and continuing on page 5, please amend the following paragraph:

"BRIEF DESCRIPTION OF THE DRAWINGS

FIGS. 1 and 2 show a cross section drawings of a prior art laser chamber.

~~FIG. 2A shows a cross section of a part of a prior art fan system for the prior art laser.~~

FIG. 3 shows a circuit diagram of a prior art pulse power system.

FIG. 4 shows a system for using the present invention as a light source for reticle writing.

FIG. 5 is a block diagram of a preferred embodiment of the present invention.

FIG. 6 is a cross section drawing of a laser chamber of a preferred embodiment.

FIG. 7 is a cross section drawing of a portion of the FIG. 6 laser chamber.

FIG. 8 is an electrical drawing of a pulse power system for a preferred embodiment.

FIG. 9 shows a preferred resonant cavity.

FIG. 10 shows the effects of reduced laser head induction.

FIG. 11 shows a technique for jitter control."